

Form PTO-1449				ATTY. DOCKET NO. 0171-1100PUS1		APPLICATION NO. NEW			
INFORMATION DISCLOSURE CITATION IN AN APPLICATION (Use several sheets if necessary)				APPLICANT Takeru WATANABE et al.					
				FILING DATE May 20, 2004		GROUP			
U.S. PATENT DOCUMENTS									
EXAMINER INITIAL	DOCUMENT NUMBER	Kind	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE		
J	US 5,691,100	A	1997-11-25	Kudo et al.					
	US 5,525,453	A	1996-06-11	Przybilla et al.					
	US 5,843,319	A	1998-12-01	Przybilla et al.					
	US 5,612,169	A	1997-03-18	Eichhorn et al.					
	US 5,442,087	A	1995-08-15	Eichhorn et al.					
	US 5,529,886	A	1996-06-25	Eichhorn et al.					
	US 6,703,181	A	2004-03-09	Hayashi et al.					
	US 5,658,706	A	1997-08-19	Niki et al.					
	US 5,744,281	A	1998-04-28	Niki et al.					
	US 6,004,724	A	1999-12-21	Yamato et al.					
FOREIGN PATENT DOCUMENTS									
	Office	DOCUMENT NUMBER	Kind	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION	
								YES	NO
J	JP	2-27660	B2	1990-06-19	JAPAN			ABS	
	JP	63-27829	A	1988-02-05	JAPAN			ABS	
	JP	5-232706	A	1993-09-10	JAPAN			ABS	
	JP	5-249683	A	1993-09-28	JAPAN			ABS	
	JP	5-158239	A	1993-06-25	JAPAN			ABS	
	JP	5-249662	A	1993-09-28	JAPAN			ABS	
	JP	5-257282	A	1993-10-08	JAPAN			ABS	
	JP	5-289322	A	1993-11-05	JAPAN			ABS	
	JP	5-289340	A	1993-11-05	JAPAN			ABS	
OTHER DOCUMENTS (Include Name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.)									
JA	HINSBERG et al., "Fundamental studies of airborne chemical contamination of chemically amplified resists", Journal of Photopolymer Science and Technology, Vol. 6, No. 4, 1993, 535-546.								
	KUMADA et al., "Study on over-top coating of positive chemical amplification resists for KrF excimer laser lithography", Journal of Photopolymer Science and Technology, Vol. 6, No. 4, 1993, 571-574.								
↓	HATAKEYAMA et al., "Investigation of discrimination enhancement with new modeling for poly-hydroxystyrene positive resists", Journal of Photopolymer Science and Technology, Vol. 13, No. 4, 2000, 519-524.								
EXAMINER J-CL					DATE CONSIDERED 9/2005				
EXAMINER: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.									

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EXAMINER INITIAL	DOCUMENT NUMBER	Kind	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
js	US 6,261,738	B1	2001-07-17	Asakura et al.			
FOREIGN PATENT DOCUMENTS							
	Office	DOCUMENT NUMBER	Kind	DATE	COUNTRY	CLASS	SUB CLASS TRANSLATION YES NO
js	JP	6-194834	A	1994-07-15	JAPAN		ABS
	JP	6-242605	A	1994-09-02	JAPAN		ABS
	JP	6-242606	A	1994-09-02	JAPAN		ABS
	JP	6-263716	A	1994-09-20	JAPAN		ABS
	JP	6-263717	A	1994-09-20	JAPAN		ABS
	JP	6-266100	A	1994-09-22	JAPAN		ABS
	JP	6-266111	A	1994-09-22	JAPAN		ABS
	JP	7-128859	A	1995-05-19	JAPAN		ABS
	JP	7-92678	A	1995-04-07	JAPAN		ABS
	JP	7-92680	A	1995-04-07	JAPAN		ABS
	JP	7-92681	A	1995-04-07	JAPAN		ABS
	JP	7-120929	A	1995-05-12	JAPAN		ABS
	JP	7-134419	A	1995-05-23	JAPAN		ABS
	JP	2000-314956	A	2000-11-14	JAPAN		ABS
	JP	9-95479	A	1997-04-08	JAPAN		ABS
	JP	9-230588	A	1997-09-05	JAPAN		ABS
	JP	9-208554	A	1997-08-12	JAPAN		ABS
EXAMINER <i>JCH</i>					DATE CONSIDERED 9/2005		
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